



UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Adress: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/591,718	09/05/2006	Keita Ishiduka	1608-7 PCT/US	3280
23869	7590	07/28/2008	EXAMINER	
HOFFMANN & BARON, LLP 6900 JERICHO TURNPIKE SYOSSET, NY 11791			JOHNSON, CONNIE P	
ART UNIT	PAPER NUMBER			
	1795			
MAIL DATE	DELIVERY MODE			
07/28/2008	PAPER			

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Office Action Summary	Application No. 10/591,718	Applicant(s) ISHIDUKA ET AL.
	Examiner CONNIE P. JOHNSON	Art Unit 1795

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED. (35 U.S.C. § 133).

Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 05 September 2006.

2a) This action is FINAL. 2b) This action is non-final.

3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 1-13 is/are pending in the application.

4a) Of the above claim(s) _____ is/are withdrawn from consideration.

5) Claim(s) _____ is/are allowed.

6) Claim(s) 1-13 is/are rejected.

7) Claim(s) _____ is/are objected to.

8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.

10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).

11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).

a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) Notice of References Cited (PTO-892)
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
 3) Information Disclosure Statement(s) (PTO/DS/02)
 Paper No(s)/Mail Date 9/5/2006

4) Interview Summary (PTO-413)
 Paper No(s)/Mail Date. _____

5) Notice of Informal Patent Application

6) Other: _____

DETAILED ACTION

Claim Status

1. Claims 1-13 are presented.

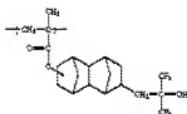
Claim Rejections - 35 USC § 103

2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

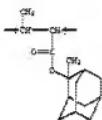
(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

3. Claims 1-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kanna et al., U.S. Patent Publication No. 2004/0009430 A1.

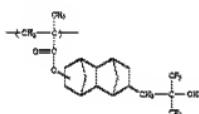
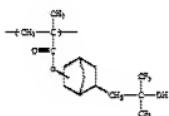
Kanna teaches a positive resist composition comprising a resin with a recurring group that decomposes by action of an acid to become soluble in alkali developer (page 2, [0018]). The recurring unit comprises divalent and trivalent cyclic groups (a1) (page 21). Examples of the (a1) groups are shown below:



Recurring units that meet the limitations of (a2) are on page 36 of the reference:



Recurring unit (a3) comprises the following unit on page 37:



The positive resist composition also comprises a photoacid generator (page 49, [0342]).

The method of forming a positive resist composition comprises applying the resist composition to a support, subjecting the resist to exposure, baking and developing the resist (page 71, [0423]). The combination of recurring units (a1), (a2) and (a3) is not exemplified in the reference. However, it would have been obvious to one of ordinary skill in the art to combine the recurring units because Kanna teaches recurring units combined in any combination as shown increases solubility of the resin in an alkali developer, has less line edge roughness and less development time (page 1, [0013]).

4. Claims 1, 12 and 13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kanna et al., U.S. Patent Publication No. 2004/0009430 A1 in view of Kawashima et al., U.S. Patent Publication No. 2004/0119954 A1.

Kanna teaches a positive resist composition comprising a resin that decomposes by action of an acid to become soluble in alkali developer and a photoacid generator. Kanna also teaches a method of forming the composition. Kanna does not teach that the resist composition may be formed by immersion exposure.

However, Kawashima teaches an immersion exposure method comprising water as the immersion liquid using an ArF laser (page 10, [0125]). Kanna also teaches exposure of a resist composition with an ArF laser. It would have been obvious to one of ordinary skill in the art to use immersion exposure in the composition of Kanna because immersion exposure enhances performance in forming patterns and prevents deteriorating image performance (page 2, [0020]).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to CONNIE P. JOHNSON whose telephone number is (571)272-7758. The examiner can normally be reached on 7:30am-4:00pm Monday thru Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Connie P. Johnson
Examiner
Art Unit 1795

/Amanda C Walke/
Primary Examiner, Art Unit 1795